

# BLACK PEELING MASK

Cosphatec

100.26.2.2

PURIFYING. DETOXIFYING. FREE OF LISTED PRESERVATIVES.

ALL NATURAL  
INGREDIENTS

**Alternative preservation: Cosphaderm® LA-T, Cosphaderm® Magnolia Extract 98**

Phase	Ingredient	COSMOS	INCI	Supplier	%
A	Demin. Water		Aqua	-	53.95
A	Kaolin		Kaolin	-	10.00
A	Glycerin		Glycerin	CREMER OLEO GmbH & Co. KG	8.00
A	Plantacare® 818 UP		Coco Glucoside	BASF SE	3.00
A	Charcoal Powder		Charcoal Powder	-	2.85
A	Cinnamic Acid		Cinnamic Acid	-	0.30
A	Cosphaderm® LA-T	✓	Levulinic Acid, Glycerin, Sodium Levulinate, Aqua	Cosphatec GmbH	1.20
A	Cosphaderm® X 34	✓	Xanthan Gum	Cosphatec GmbH	0.40
B	Mango Butter		Mangifera Indica Seed Butter	-	6.00
B	PolyAquil®-2W		Polyglyceryl-2 Stearate, Glyceryl Stearate, Stearyl Alcohol	Innovacos	2.50
B	Beeswax		Cera alba	Gustav Heess GmbH	2.50
B	Ecorol® 16/98 P		Cetyl Alcohol	Ecogreen Oleochemicals	2.00
B	Cosphaderm® Feel	✓	Triheptanoïn	Cosphatec GmbH	1.00
B	Cosphaderm® T-70 NON GMO ECO	✓	Tocopherol, Helianthus Annuus Seed Oil	Cosphatec GmbH	0.10
C	Cosphaderm® Magnolia Extract 98	✓	Magnolia Officinalis Bark Extract	Cosphatec GmbH	0.20
D	Kaolin		Kaolin	-	5.00
D	Lipo® AMS		Prunus Amygdalus Dulcis Seed Meal	Vantage Speciality Ingredients, Inc.	1.00

## Manufacturing Process

Phase A: Combine all ingredients of phase A and raise the pH to 11 to dissolve the cinnamic acid completely. Afterwards, adjust the pH to  $5.5 \pm 0.05$  by adding Citric Acid.

Phase B: Prepare phase B and heat phase A and phase B separately to 75 °C.

Add phase B to phase A under thorough stirring with the propeller stirrer and homogenise the mixture.

Phase C: Add Cosphaderm® Magnolia Extract 98 to phase A+B under stirring and below 40 °C.

Phase D: Prepare phase D and add it to the formulation. Let the mask cool down under moderate stirring. Adjust the pH to  $5.5 \pm 0.05$ .

## Specification

Appearance: Black, creamy paste with small exfoliants

pH:  $5.5 \pm 0.05$

Stability: Microbiological stability proven, no separation after centrifugation (4000 rpm, 30 min)

Disclaimer: This information and our technical application advice are given to the best of our knowledge, but it is for information purposes only and no responsibility is assumed.